

**LITHOGRAPHIC PHOTOMASK AND METHOD OF MANUFACTURE TO
IMPROVE PHOTOMASK TEST MEASUREMENT**

ABSTRACT OF THE DISCLOSURE

5 A photomask for use in a lithographic process and a method of making a
photomask are disclosed. A mask blank including a substrate, a sacrificial
conductive layer disposed over the substrate and a radiation shielding layer
disposed over the sacrificial conductive layer can be provided. Structures are
then formed from the radiation shielding layer to define a pattern. Measurement
10 of parameters associated with the structures are made with a measurement tool
and, during the measuring, the sacrificial conductive layer provides a conductive
plane to dissipate charge transferred to the mask by the measurement tool.

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